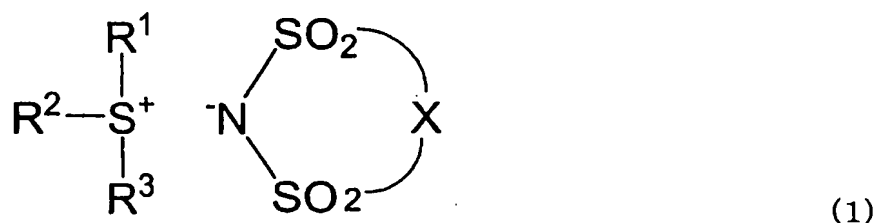


ABSTRACT

A photoresist composition is provided, that includes

(A) a polymer component including an alkaline-soluble constitutional unit that contains an aliphatic cyclic group having both (i) a fluorine atom or a fluorinated alkyl group and (ii) an alcoholic hydroxide group; in which the alkaline solubility of the polymer component may be changed by action of an acid; and

(B) an acid generating component, capable of generating an acid by way of exposure, that contains at least a sulfonium compound expressed by the general formula (1) below;



in the formula (1), X represents a C2 to C6 alkylene group of which at least a hydrogen atom is substituted by a fluorine atom; R^1 to R^3 represent independently of each other an aryl or alkyl group, and at least one of R^1 to R^3 represents an aryl group.